CLAIMS

1. An organic processing liquid for patterning a chemical amplification resist film,

wherein the organic processing liquid contains 1 ppm or less of alkylolefin having a carbon number of 22 or less, and 5 ppm or less of a metal element concentration of each of Na, K, Ca, Fe, Cu, Mg, Mn, Li, Al, Cr, Ni, and, Zn.

2. The organic processing liquid according to claim 1,

wherein the organic processing liquid is an organic developer.

3. The organic processing liquid according to claim 2,

wherein the organic developer contains at least one selected from the group consisting of a ketone-based solvent, an ester-based solvent, an alcohol-based solvent, an amide-based solvent and an ether based solvent.

~~3~~4. The organic processing liquid according to claim 2,

wherein the organic developer is butyl acetate.

~~4~~5. The organic processing liquid according to claim 1,

wherein the organic processing liquid is an organic rinsing liquid.

6. The organic processing liquid according to claim 5,

wherein the organic rinsing liquid is selected from the group consisting of a ketone-based solvent, an ester-based solvent, an alcohol-based solvent, and an amide-based solvent.

~~5~~7. The organic processing liquid according to ~~claim 4~~ claim 5,

wherein the organic rinsing liquid is 4-methyl-2-pentanol or butyl acetate.

~~6~~8. A container of an organic processing liquid for patterning a chemical amplification resist film, the container comprising a housing portion in which the organic processing liquid according to any one of ~~claims 1 to 5~~ claims 1 to 7 is contained,

wherein the housing portion has an inner wall to come in contact with the organic processing liquid, the inner wall being made from:

a resin different from at least one kind of resin selected from the group consisting of a polyethylene resin, a polypropylene resin, and a polyethylene-polypropylene resin; or

a metal subjected to a rust-prevention/metal elution prevention treatment.

~~7~~9. The container according to ~~claim 6~~ claim 8,

wherein the resin different from the at least one kind of resin selected from the group consisting of a polyethylene resin, a polypropylene resin, and a polyethylene-polypropylene resin is a perfluoro resin.

~~8~~10. A pattern forming method comprising:

(A) forming a film from a chemical amplification resist composition;

(B) exposing the film; and

(C) developing the exposed film using an organic developer,

wherein the organic developer is the organic processing liquid according to ~~claim 2 or 3~~ any one of claims 2 to 4.

~~9~~11. The pattern forming method according to ~~claim 8~~ claim 10, further comprising:

performing a washing by using an organic rinsing liquid after the developing of the exposed film using the organic developer,

wherein the organic rinsing liquid is the organic processing liquid ~~according to claim 4 or 5~~ any one of claims 5 to 7.

~~10~~12. The pattern forming method according to ~~claim 9~~ claim 11,

wherein the organic developer is the organic processing liquid for patterning a chemical amplification resist film according to ~~claim 3~~ claim 4, and

the organic rinsing liquid is the organic processing liquid for patterning a chemical amplification resist film according to ~~claim 5~~ claim 7.

~~11~~13. The pattern forming method according to any one of ~~claims 8 to 10~~ claims 10 to 12,

wherein the developing of the exposed film using the organic developer is performed by using a developing apparatus mounted with a filter for a processing liquid, and

the organic developer passes through the filter for the processing liquid.

~~12~~14. A method of manufacturing an electronic device, the method comprising the pattern forming method according to any one of claims ~~8 to 11~~ 10 to 13.

~~13~~15. An electronic device manufactured by the method according to ~~claim 12~~ claim 14.